

## REMARKS

Reconsideration of this application, as amended, is respectfully requested.

Applicants affirm election of claims 22 and 23 for prosecution.

Claims 24 to 26 have been canceled.

Claims 21 and 22 have been amended to overcome all 35 U.S.C. §112 rejections thereof.

All objections have been addressed by the submission of new drawings and by the amendments to the specification.

Claim 22 was rejected as allegedly obvious over Latz in view of Szcyrbowski and Vossen. Claim 23 was rejected as allegedly obvious over Scherer in view of Vossen. Applicants respectfully traverse each of these rejections.

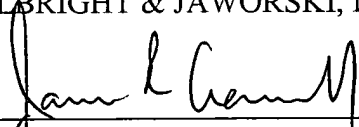
Vossen describes the relationship between the power applied to the target and the position rate in a very general way which does not completely apply to the specific two-cathode-arrangement of the presently claimed invention. As already indicated by Vossen, there are several other parameters than power influencing the deposition rate, as system geometry, target voltage, sputtering gas, gas pressure etc. Thus, particularly for a two-cathode-arrangement, it is not obvious at all to choose the power in order to obtain the claimed deposition rate.

This can also be seen from the fact that Scherer only report of a deposition rate up to 3.8 nm/s. Thus, the invention the claims choose the power of the targets to arrive at a deposition rate of  $> 4\text{nm/s}$  or to choose a deposition rate of  $\geq 400\text{ nm m/min}$  is not obvious for itself a man skilled in the art.

Additionally, it is not the objet of the present invention to achieve a high deposition rate, but to use a high deposition rate to produce metal oxide layers on substrates with high optical quality on an industrially applicable scale. In particular, it is an object of the present invention to achieve layers having a very smooth surface. None of the cited references suggests to choose the output power of cathodes or the deposition rate to produce the required metal oxide layers with high optical quality and a very smooth surface.

If any additional fees are due, authorization is given to charge deposit account no: 50-0624.

Respectfully submitted,  
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Petition for Extension of Time and fee